Occket No.: 50090-334

IN THE UNITED STATES PATENT AND TRADEMARK OFFI

TECHNOLOGY CENTER R3700

re Application of

Masanobu IWASAKI, et al.

Serial No.: 09/934,474

Filed: August 23, 2001

Examiner: H. Shakeri

POLISHING SOLUTION SUPPLY SYSTEM, METHOD OF SUPPLYING For:

POLISHING SOLUTION, APPARATUS FOR AND METHOD OF POLISHING SEMICONDUCTOR SUBSTRATE AND METHOD OF MANUFACTURING

SEMICONDUCTOR DEVICE

AMENDMENT UNDER 37 CFR §1.116

Commissioner for Patents Washington, DC 20231

Sir:

The following Amendment and Remarks are submitted in response to the Office Action dated April 18, 2002, pursuant to the provisions of 37 C.F.R. §1.116.

IN THE CLAIMS:

Please amend claims 3, 5 and 10 as follows.

(Twice Amended) The apparatus according to claim 1, wherein each of 3. said supply units comprises:

a tank for storing liquid;

a pipe for supplying said liquid from said tank to said mixing unit;

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